Special Issue

Plasma Combustion and Flow Control Processes

Message from the Guest Editors

This Special Issue on "Plasma Combustion and Flow Control Processes" seeks high-quality works, focusing on the latest plasma technologies for plasma-assisted combustion, enhanced ignition, and flow control. Topics include but are not limited to:

- Application of plasma in the combustion of new fuels;
- Mechanism of plasma-assisted combustion and enhanced ignition;
- Plasma flow control processes, including reseach on the boundary layer, vortex, shock wave, ion wind, flow illustration, etc.;
- Diagnostic methods related to plasma combustion and flow control.

Guest Editors

Prof. Dr. Xi-Ming Zhu

Prof. Dr. Ming Zhai

Dr. Bang-Dou Huang

Deadline for manuscript submissions

closed (31 December 2022)



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Message from the Editor-in-Chief

You are invited to contribute either a research article or a comprehensive review for consideration and publication in *Processes* (ISSN 2227-9717). *Processes* is published in open access format – research articles, reviews, and other content are released on the internet immediately after acceptance. The scientific community and the general public have unlimited, free access to the content. As an open access journal, *Processes* is supported by the authors and their institutes through the payment of article processing charges (APCs) for accepted papers. We would be pleased to welcome you as one of our authors.

Editor-in-Chief

Prof. Dr. Giancarlo Cravotto

Department of Drug Science and Technology, University of Turin, Via P. Giuria 9, 10125 Turin, Italy

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